

Amendments to the Specification

Please replace the paragraph on page 3, line 24 to page 4, line 3, with the following amended paragraph:

Figure [[2]] **1** is a schematic of a system, generally designated by the numeral **2**, for use in practicing the present invention. The system **2** includes source **4** of a silica precursor **6**. There are many choices available for the silica precursor, *e.g.*, a siloxane such as OMCTS ($\text{Si}_4\text{O}_4(\text{CH}_3)_8$), halogen-based precursors such as silicon tetrachloride (SiCl_4), silane (SiH_4), and other silicon-containing compounds. In general, halogen-free precursors are preferred because they are more environmentally friendly. Silane exists in vapor form at room temperature and does not need a vaporization step prior to mixing with the titania precursor. The silica precursor **6** is pumped into the source **4** at a predetermined rate. The source **4**, which may be a vaporizer or evaporator tank or similar equipment, converts the silica precursor **6** into vapor form if the silica precursor **6** is not already in vapor form. An inert carrier gas **8**, *e.g.*, nitrogen, carries the silica precursor **6** vapors through a distribution system **12** to a manifold **14**. A stream of inert gas **10**, *e.g.*, nitrogen, is brought into contact with the silica precursor **6** vapors to prevent saturation.